# **High Temperature Photovoltaic Effect at Nb Doped SrTiO<sub>3</sub>/Electrode** F. Horikiri, T. Ichikawa, A. Kaimai,

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### Introduction

Electronic properties at the interface between electrode and  $SrTiO_3$  (STO) are important in various advanced devices such as VLSI [1], DRAM [2] etc. As is well known, Schottky barrier exists at the interface between an electrode and a semiconductor. Many studies have been made on the barrier formation at the metal/STO interfaces [3-5]. So far, however, very few attempts have been made to study its high temperature characteristics.

Recently, the authors found that a finely prepared interface on a donor doped STO single crystal shows a clear rectification effect even at elevated temperatures up to 873K[6].

In this study, we investigated the photovoltaic effect of Nb doped STO/electrode interface in various  $P_{O2}$  at high temperatures in order to confirm existence of Schottky barrier at high temperatures.

## Experimental

Single crystal disks, 16mm in diameter and 0.5mm in thickness, of nominal 0.01 wt% Nb doped SrTiO3 (STNO) (100) were supplied by Nakazumi Crystal Laboratory. Surfaces of the disks were polished to an optical level. As the working electrode (WE), ITO  $(In_2O_3:SnO_2 = 95:5 \text{ wt\%})$  was deposited on STNO by a Pulsed Laser Deposition technique (PLD). As the counter electrode, Pt was deposited for the current collector. Laheavily doped SrTiO<sub>3</sub> (La<sub>0.1</sub>Sr<sub>0.9</sub>TiO<sub>3</sub>: LSTO) layer was deposited between Pt and STNO to attain ohmic contact. For PLD, substrate temperature was kept at 873K. The chamber was filled with O2 of approximately 1 bar for oxide electrode deposition, and evacuated to approximately 10<sup>-4</sup> bar for metal electrodes. Schematics of electrodes on the sample are shown in Fig. 1. I-V characteristics were measured using a potentiostat/FRA instrument (ECOCHEMIE Co., PGSTAT30). Ultraviolet (UV) light was irradiated to the interface from the ITO side. An UV spot light source (USHIO Inc, SPOT-CURE<sup>®</sup> SP-7) with band pass filter (365 nm) was used.



Fig. 1 Schematic view of the sample.

#### **Results ant Discussion**

Current-voltage (I-V) characteristics of ITO/STNO interface at high temperatures are shown in Fig. 2. The interface showed rectification effect that is caused by Schottky barrier. The rectification effect depended on  $P_{02}$ . This is consistent with our previous results for the other electrode materials; i.e. the barrier formation mechanism essentially follows Bardeen model [7].

I-V characteristics of ITO/STNO interface that was irradiated by UV light is shown in Fig. 3. The interface showed photovoltaic effect even at high temperatures. It is a strong evidence of existence of Schottky barrier at the interface even at high temperatures.

In Fig. 3, intercepts of x-axis and y-axis correspond to open circuit voltage (OCV) and short circuit current (SCC), respectively. OCV and SCC are unexpectedly high, approximately 200 mV and 2 mA cm<sup>-2</sup>, respectively at 673K. From Fig. 3 OCV increases and SCC decreases with the increase in  $P_{02}$ . This is consistent with the observed  $P_{02}$  dependence of the rectification effect.



Voltage/V Fig. 2 I-V characteristics of ITO/STNO interface at high temperatures.



Fig. 3 I-V characteristics of ITO/STNO interface at high temperatures under  $484 \text{ mW cm}^{-2} \text{ UV}$ .

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